	ū	11.	Document ID	Issue Date	Pages	Title	Current OR	Current XRef	Retrieval Classif
1		⋈	US 6193507 B1	20010227	16	Multi-function chamber for a substrate processing system	432/247	118/724 ; 118/725 ; 432/184	
2		M	US 6183183 B1	20010206	19	Dual arm linear hand-off wafer transfer assembly	414/217	118/719 ; 294/64.3 ; 414/225.01 ; 414/752.1 ; 414/939 ; 414/941	
3		⋈	US 6176668 B1	20010123	26	In-situ substrate transfer shuttle	414/217	198/346.2 ; 414/939	
4		⋈	US 6162299 A	20001219	18	Multi-position load lock chamber	118/719	414/217 ; 414/936 ; 414/937 ; 414/939	
رى		⋈	US 6158941 A	20001212	12	Substrate transport apparatus with double substrate holders	414/222.12	294/87.1 ; 414/937	
b		⋈	US 6152070 A	20001128	43	Tandem process chamber	118/719	118/723MP	***************************************
, ,		M	US 6151447 A	20001121	62	Rapid thermal processing apparatus for processing semiconductor wafers	392/418	118/728 ; 118/730 ; 219/390 ; 219/411	
8		⋈	US 6120229 A	20000919	18	Substrate carrier as batchloader	414/217	414/937; 414/940	
ത		M	US 6122566 A	20000919	21	Method and apparatus for sequencing wafers in a multiple chamber, semiconductor wafer	700/218	438/908 ; 700/228	
10		M	US 6109677 A	20000829	. 8	; —	294/103.1	294/119.1 ; 414/941 ; 901/39	

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1 [1 Document ID]	Documen	it ID	Issue Date	Pages	Title	Current OR	Current XR f	Retrieval Classif
US 6086362 A			20000711	16	Multi-function chamber for a substrate processing system	432/243	118/724 ; 118/725 ; 432/247	
K US 6042623 A	6042623		20000328		Two-wafer loadlock wafer processing apparatus and loading and unloading method therefor	29/25.01	204/298.26 ; 414/217 ; 414/217.1 ; 414/416 ; 414/937 ; 414/939 ; 438/908	
US 5981399 A	5981399		19991109		Method and apparatus for fabricating semiconductor devices	438/715	156/345 ; 438/716	
US 5951770 A	5951770		19990914		Carousel wafer transfer system	118/719	118/724 204/298.25 204/298.35 414/217 414/223.01 414/225.01 414/403 414/403 414/403 414/403 414/403 414/905 414/935 414/939 414/939	

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	Ω	1 [1]	Document ID	Issu Date	Pages	Title	Current OR	Current XR f	R trieval Classif
15	M	≅	US 5882413 A	19990316		Substrate processing apparatus having a substrate transport with a front end extension and an internal substrate buffer	118/719	118/724 ; 118/725 ; 134/1.1 ; 134/22.1 ; 156/345 ; 204/298.25 ; 204/298.35 ; 414/936 ; 414/936 ; 414/937	
16	M	M	US 5738767 A	19980414		Substrate handling and processing system for flat panel displays	204/192.12	204/298.25 ; 204/298.28 ; 414/214 ; 414/222.13	
17	M	M	US 5607009 A	19970304		Method of heating and cooling large area substrates and apparatus therefor	165/48.1	118/725 ; 165/61 ; 165/80.5	
18	M	M	US 4951601 A	19900828		Multi-chamber integrated process system	118/719	118/715 ; 118/729 ; 204/298.25 ; 414/217 ; 414/935 ; 414/937	

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